

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	13483	134/1,2,26,29,902.cds. 355/53.cds.	US-PGPUB; USPAT	OR	ON	2009/02/11 12:28
L2	267	1 and ((immersion near3 lithography)) and ((clean\$3 or wash\$3 or remov\$3 or treat\$5) same (len or optical or optic))	US-PGPUB; USPAT	OR	ON	2009/02/11 12:28
L3	17	2 and ("h.sub.2o.sub.2" or "hydrogen peroxide" or ozone or "o.sub.3")	US-PGPUB; USPAT	OR	ON	2009/02/11 12:29
S2	2	"20050205108".pn.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/02/09 14:58
S3	1	"7420188".pn.	US-PGPUB; USPAT	OR	ON	2009/02/09 15:03
S4	1	"7056646".pn.	US-PGPUB; USPAT	OR	ON	2009/02/09 15:05
S6	2	"20060023185".pn.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/02/09 15:24
S7	1	"6788477".pn.	US-PGPUB; USPAT	OR	ON	2009/02/09 15:26
S8	1	"5368649".pn.	US-PGPUB; USPAT	OR	ON	2009/02/09 15:31
S9	2	"6496257".pn. "5368649". pn.	US-PGPUB; USPAT	OR	ON	2009/02/09 15:41
S11	4	"874283".pn.	FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/02/09 15:41
S15	840	((immersion near3 lithography)) and ((clean\$3 or wash\$3 or remov\$3 or treat\$5) same (len or optical or optic))	US-PGPUB; USPAT	OR	ON	2009/02/09 16:02
S16	18	S15 and "134".das.	US-PGPUB; USPAT	OR	ON	2009/02/09 16:02

S17	70	((immersion near3 lithography)) and ((clean\$3 or wash\$3 or remov\$3 or treat\$5) same (len or optical or optic))	FPFS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/02/09 16:21
S18	0	S17 and b08b\$/\$.ipc.	FPFS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/02/09 16:21
S19	11	S17 and h01\$/\$.ipc.	FPFS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/02/09 16:21
S20	32	((immersion near3 lithography) same (clean\$3 or wash\$3 or remov\$3 or treat\$5) same (len or optical or optic))	FPFS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/02/09 16:21
S21	59	S17 not S19	FPFS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/02/09 16:39
S22	30	S21 not S20	FPFS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/02/09 16:39
S23	1	"4046706".pn.	US-PGPUB; USPAT	OR	ON	2009/02/09 16:53
S24	46	("20010002315" "3648587" "4057347" "4480910" "5121256" "5139661").PN. OR ("6788477").URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2009/02/09 17:05
S25	1	"7056646".pn.	US-PGPUB; USPAT	OR	ON	2009/02/09 18:15
S26	5	"2004093130".pn.	US-PGPUB; USPAT; USOCR; FPFS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/02/09 18:19
S27	1	"7070915".pn.	US-PGPUB; USPAT	OR	ON	2009/02/09 18:37
S28	11	((immersion near3 lithography)) same expos\$3 same surfactant same (liquid or fluid)	US-PGPUB; USPAT	OR	ON	2009/02/09 19:14
S29	2	"20050164502".pn. "20050161644".pn.	US-PGPUB; USPAT	OR	ON	2009/02/10 09:55

S30	51	(immersion near3 lithography) and (immersion same (fluid or liquid) same surfactant)	US-PGPUB; USPAT	OR	ON	2009/02/10 09:57
S31	111	((immersion near3 lithography) same (clean\$3 or wash\$3 or remov\$3)) and (surfactant)	US-PGPUB; USPAT	OR	ON	2009/02/10 11:13
S32	8	S31 and "134".das.	US-PGPUB; USPAT	OR	ON	2009/02/10 11:14
S33	8	((immersion near3 lithography) same (clean\$3 or wash\$3 or remov\$3)) and (surfactant)	FPFS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/02/10 11:14
S34	14	S31 and @ad< "20040316"	US-PGPUB; USPAT	OR	ON	2009/02/10 11:15
S35	5	(lithography same (clean\$3 or wash\$3 or remov\$3) same (len or optical)) and (surfactant)	FPFS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/02/10 11:19
S36	213	(lithography same (clean\$3 or wash\$3 or remov\$3) same (len or optical)) and (surfactant)	US-PGPUB; USPAT	OR	ON	2009/02/10 11:20
S37	8	S36 and "134".das.	US-PGPUB; USPAT	OR	ON	2009/02/10 11:20
S38	493	(lithography same (clean\$3 or wash\$3 or remov\$3) same (len or optical)) and ("nh.sub.4oh" or "ammonium hydroxide" or ozone or "o.sub.3" or "hydrogen peroxide" or "h.sub.2o.sub.2")	US-PGPUB; USPAT	OR	ON	2009/02/10 11:55
S39	19	S38 and "134".das.	US-PGPUB; USPAT	OR	ON	2009/02/10 11:55
S40	13	(lithography same (clean\$3 or wash\$3 or remov\$3) same (len or optical)) and ("nh.sub.4oh" or "ammonium hydroxide" or ozone or "o.sub.3" or "hydrogen peroxide" or "h.sub.2o.sub.2")	FPFS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/02/10 11:57
S41	10	(lithography same (clean\$3 or wash\$3 or remov\$3) same (len or optical)) and (ozone or "o.sub.3" or "hydrogen peroxide" or "h.sub.2o.sub.2")	FPFS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/02/10 12:20

S42	393	((lithography same (clean\$3 or wash\$3 or remov\$3) same (len or optical)) and (ozone or "o.sub.3" or "hydrogen peroxide" or "h.sub.2o.sub.2"))	US-PGPUB; USPAT	OR	ON	2009/02/10 12:20
S43	19	S42 and "134".das.	US-PGPUB; USPAT	OR	ON	2009/02/10 12:20
S44	165	surfactant same hydrophilic same wafer	US-PGPUB; USPAT	OR	ON	2009/02/10 13:03
S45	4	S44 and (immersion near3 lithography)	US-PGPUB; USPAT	OR	ON	2009/02/10 13:04
S46	65	surfactant with hydrophilic with wafer	US-PGPUB; USPAT	OR	ON	2009/02/10 13:09
S47	2	"9949504".pn.	FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/02/10 14:18
S48	10	((immersion near3 lithography) same ((deionized or "de-ionized") near2 water))	FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/02/10 14:20
S49	157	((immersion near3 lithography) same ((deionized or "de-ionized") near2 water))	US-PGPUB; USPAT	OR	ON	2009/02/10 14:22
S51	1	"7315033".pn.	US-PGPUB; USPAT	OR	ON	2009/02/10 16:06
S52	11	("20040125351" "20040207824" "20040257544" "20050007570" "20050018155" "20050024609" "20050078286" "20060132731" "6466365" "6496257" "7145641").PN. OR ("7315033").URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2009/02/10 16:06
S54	4	S52 and (ozone or "o.sub.3" or "hydrogen peroxide" or "h.sub.2o.sub.2")	US-PGPUB; USPAT	OR	ON	2009/02/10 16:07
S56	2	"7315033".pn.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/02/10 16:12

S58	747	((clean\$3 or remov\$3 or wash\$3) same (len or optical)) and (ozone or "o.sub.3" or "hydrogen peroxide" or "h.sub.2o.sub.2")	FPRS, EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/02/10 16:20
S61	25	S58 and b08b\$/ \$ ipc.	FPRS, EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/02/10 16:23
S73	25	("4021120" "4074217" "4365877" "4365896" "4896047" "5088083" "5229602" "5812270" "5929981" "6268904"). PN. OR ("6496257").URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2009/02/10 16:34
S77	21	((clean\$3 or remov\$3 or wash\$3) same (len or optical)) and ((ozone or "o.sub.3") same ("hydrogen peroxide" or "h.sub.2o.sub.2"))	FPRS, EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/02/10 16:56
S78	3	"7119878".pn.	US-PGPUB; USPAT; USOCR; FPRS, EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/02/10 17:00
S79	633	((clean\$3 or remov\$3 or wash\$3) same (len or optical)) and ((ozone or "o.sub.3") same ("hydrogen peroxide" or "h.sub.2o.sub.2"))	US-PGPUB; USPAT	OR	ON	2009/02/10 17:02
S80	87	S79 and "134".clas.	US-PGPUB; USPAT	OR	ON	2009/02/10 17:02
S81	50	S80 and @ad< "20040316"	US-PGPUB; USPAT	OR	ON	2009/02/10 17:02
S82	1279	((clean\$3 or remov\$3 or wash\$3) same (ozone or "o.sub.3") same ("hydrogen peroxide" or "h.sub.2o.sub.2")) and (lithography or exposure)	US-PGPUB; USPAT	OR	ON	2009/02/10 17:04
S83	149	S82 and "134".clas.	US-PGPUB; USPAT	OR	ON	2009/02/10 17:05
S84	102	S83 and @ad< "20040316"	US-PGPUB; USPAT	OR	ON	2009/02/10 17:05
S85	78	S84 not S81	US-PGPUB; USPAT	OR	ON	2009/02/10 17:05

S87	2	"10289853".pn.	FPRS, EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/02/10 17:27
S92	1	"20060005857".pn.	US-PGPUB; USPAT	OR	ON	2009/02/10 17:36
S93	25	("4021120" "4074217" "4365877" "4365896" "4896047" "5088083" "5229602" "5812270" "5929981" "6268904"). PN. OR ("6496257").URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2009/02/10 17:40
S94	1	"6568995".pn.	US-PGPUB; USPAT; USOCR	OR	ON	2009/02/10 17:46
S95	663	((clean\$3 or remov\$3 or wash\$3) same (len or optical or lenses)) and ((ozone or "o.sub.3") same ("hydrogen peroxide" or "h. sub.2o.sub.2"))	US-PGPUB; USPAT	OR	ON	2009/02/10 17:48
S96	99	S95 and "134".das.	US-PGPUB; USPAT	OR	ON	2009/02/10 17:48
S97	12	S96 not S80	US-PGPUB; USPAT	OR	ON	2009/02/10 17:49
S98	1	"7119878".pn.	US-PGPUB; USPAT	OR	ON	2009/02/10 17:51
S99	6	US-20040125351-\$.DID. OR US-20040207824-\$. DID. OR US-20040257544- \$.DID. OR US- 20050007570-\$.DID. OR US-20050018155-\$.DID. OR US-20050024609-\$. DID.	US-PGPUB; USPAT	OR	ON	2009/02/10 17:54
S100	324	chang-ching-yu.in. lin-chin- hsiang.in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/02/10 18:16
S101	6	S100 and ((clean\$3 or remov\$3 or wash\$3) same (len or optical or lenses)) and ((ozone or "o.sub.3") same ("hydrogen peroxide" or "h.sub.2o.sub.2"))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/02/10 18:16
S103	17091	"taiwan semiconductor manufacturing".as	US-PGPUB; USPAT, USOCR, FPRS, EPO, JPO, DERWENT; IBM_TDB	OR	ON	2009/02/10 18:19

S104	9	S103 and ((clean\$3 or remov\$3 or wash\$3) same (len or optical or lenses)) and ((ozone or "o.sub.3") same ("hydrogen peroxide" or "h.sub.2o.sub.2"))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/02/10 18:19
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2/ 11/ 2009 12:32:25 PM

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